DOCKET: BU9-99-022B PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

T. Quach **PRIOR** Marc W. Cantell et al. **INVENTOR: EXAMINER: PRIOR ART** Divisional Application of U.S. 2814 **SERIAL NO.: UNIT:** Serial No. 09/365,859) December 27, 2000 DATE:) FILING DATE:

FOR:

OSCILLATOR WITH
DIGITALLY VARIABLE PHASE

FOR A PHASE-LOCKED LOOP

PRELIMINARY AMENDMENT

)

BOX PATENT APPLICATION

Assistant Commissioner of Patents Washington, D.C. 20231

Dear Sir:

Applicants respectfully submit the following preliminary amendment for entry in the above-identified Divisional application of pending application serial number 08/898,443.

In the Specification

On page 3, line 19, after "of" (second occurrence) insert - - a - - .

On page 3, line 23, after "invention" insert - - is - - .

On page 5, line 6, delete "comprising" and substitute therefor - - comprises - - .

On page 8, line 22, after "pressure" insert - - of - - .

On page 8, line 24, delete "in the" and substitute therefor - - of - - .

In the Claims

Please cancel claims 1-9.

Amend the following claims:

1	10. (Amended) An apparatus for forming a silicide on a surface of a
2	semiconductor substrate, [said apparatus being adapted to form a vacuum therein,
3	said apparatus further adapted to remove an oxide from said surface of saic
4	substrate and deposit a metal on said surface of said substrate while maintaining
5	said vacuum, said apparatus] comprising:
6	a chamber;
7	at least one workpiece holder within said chamber adapted to hold said
8	substrate;
9	at least one pump adapted to evacuate said chamber;
10	at least one line operatively connected between said at least one pump and
11	said chamber for evacuating said chamber;
12	at least one input line adapted to provide a chemical agent into said chamber
13	said chemical agent adapted to remove [said] an oxide from said surface o
14	said substrate;
15	at least one output line adapted to remove said cleaning agent and said
16	removed oxide from said chamber;
17	a heating element in said chamber, said heating element adapted to heat said
18	substrate to an elevated temperature; and

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a reactor in said chamber, said reactor adapted to deposit [said] a metal onto
said substrate surface

wherein said apparatus is adapted to form a continuous vacuum therein, said
apparatus further adapted to remove said oxide from said surface of said substrate
and deposit said metal on said surface of said substrate while maintaining said
continuous vacuum.

- 1 11. (Amended) The apparatus of claim 10 wherein said apparatus is further adapted to heat said substrate to form [said] <u>a</u> silicide on said surface of said substrate.
 - 12. (Amended) The apparatus of claim 10 wherein said chamber comprises a plurality of interior chambers, at least one interior chamber adapted to remove said oxide from said surface of said substrate while under said continuous vacuum, and at least one interior chamber adapted to deposit said metal on said surface of said substrate while under said continuous vacuum.
- 1 14. (Amended) The apparatus of claim 12 wherein said apparatus is adapted to 2 transfer said substrate between said interior chamber adapted to remove said oxide 3 from said surface of said substrate and said interior chamber adapted to deposit

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said metal on said surface of said substrate without breaking said continuous 4

5 vacuum.

REMARKS

The foregoing preliminary amendment (which is being mailed simultaneously with a request for filing a divisional application of pending application serial number 09/365,859) is submitted as noted above to define more specifically the invention described in this divisional application. Support for the amendments to claims 10, 12, and 14 can be found in claims 8 and 10 as originally filed. Furthermore, claims 10 and 11 have been amended to correct the dependency. The claims now pending in this divisional application are 10-20. Applicants have canceled claims 1-9. Further, Applicants have reviewed the specification and have found that the above typographical and/or clerical errors require amendment. No new matter has been added.

Respectfully submitted,

Reg. No. P47,898

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CERTIFICATION OF MAILING UNDER 37 CFR 1.10

Date of Deposit: December 27, 2000 "Express Mail" mailing label number **EL277591106US** hereby certify that this paper or fee is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 on the date indicated above and is addressed to the Assistant Commissioner for Name: Carol M. Thomas Signature: Manual Manu

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